

[DYNAMIC RELEASE WAFER GRIP AND METHOD OF USE]

Abstract

A system and method for processing a workpiece which prevents processing variations and contaminations on the workpiece. The system and method permits processing fluids to flow off a surface of the workpiece unimpeded. The method and system includes providing a plurality of contacts for holding the workpiece during a processing or fabrication. During the processing, the contacts are released from the workpiece in order to allow the fluids to flow off a surface of the workpiece. A control may be used to control the movements of the contacts toward and away from the workpiece to engage and release the workpiece, respectively.